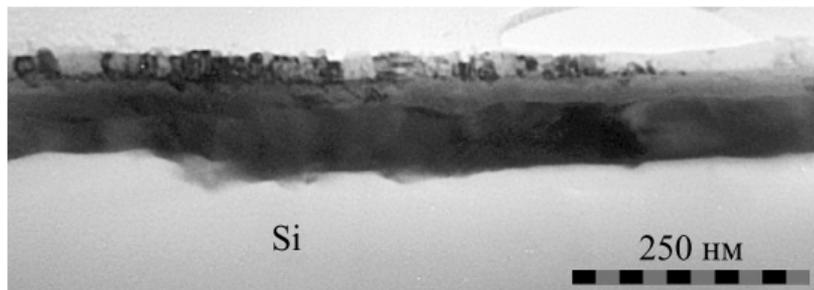
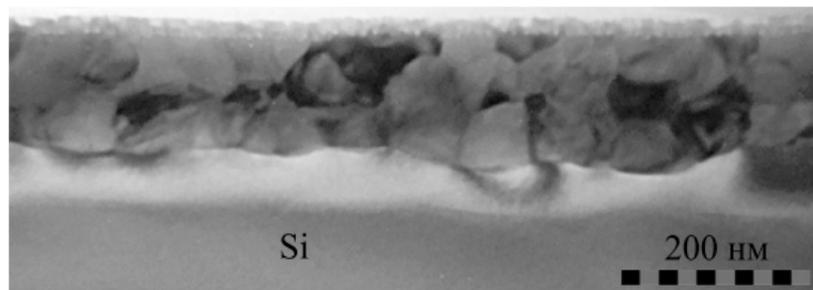
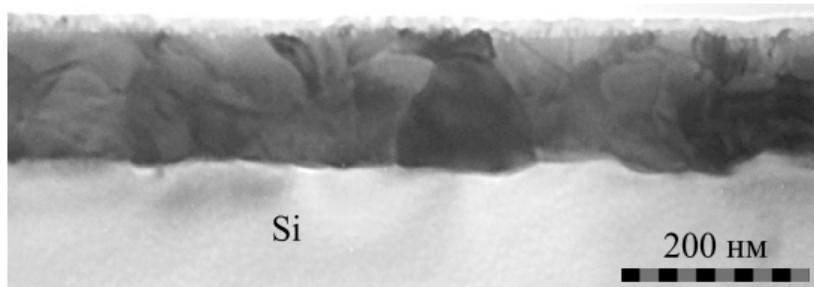
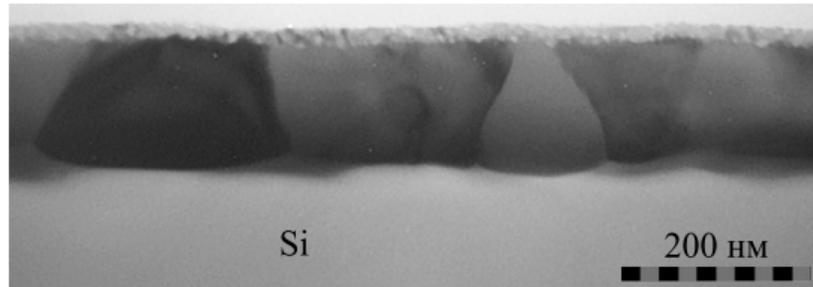


*a/a**б/б**в/с**г/д*

*Рис. 5.* Светлопольные X-ПЭМ-микрофотографии, полученные от структуры Ni – V/Pt/Si с толщиной слоя сплава Ni – V 40 нм после БТО при температуре 450 °C (*а*), 500 °C (*б*), 550 °C (*в*) и 600 °C (*г*)

*Fig. 5.* Bright-field cross-section transmission electron microscopy micrographs obtained from the Ni – V/Pt/Si structure with a Ni – V alloy layer thickness of 40 nm after rapid heat treatment at a temperature of 450 °C (*a*), 500 °C (*b*), 550 °C (*c*) and 600 °C (*d*)